Special Issue

Process Control Technologies and Their Applications in Industry

Message from the Guest Editor

Advanced control technologies have revolutionized several industrial sectors by enabling enhanced process optimization, increased efficiency, and improved product quality. This Special Issue delves into the latest developments in advanced control technologies and their wide-ranging applications in different industries. This field encompasses a diverse range of methodologies, from model predictive control (MPC) and adaptive control to advanced optimization algorithms and machine learning-based control systems. Overall, the goal of this Special Issue is to showcase the latest advancements in control technologies and their diverse applications across different industries. Whether your research focuses on model predictive control, adaptive control, optimization algorithms, or machine learning-based control systems, we encourage you to share your valuable insights and findings.

Guest Editor

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Message from the Editor-in-Chief

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